

STRUCTURE AND METHOD FOR DETERMINING EDGES
OF REGIONS IN A SEMICONDUCTOR WAFER

Abstract of the Disclosure

A method for electrically determining in a semiconductor
5 wafer the location of edges of a well that underlies an
insulating layer that includes forming in the wafer before
forming of the well and the insulating layer a plurality of
conductive stripes will that pass under the future insulating
layer and extend to varying distances under the insulating layer
so as to include stripes that will penetrate an edge to be
located so as to form a low resistance connection thereto and
stripes that will fall short of an edge to be located. From the
stripes of minimum penetration that make low resistance can be
determined the location of the well edges.

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